Ref #	Hits	Search Query	DBs .	Default Operator	Plurals	Time Stamp
S1	2558	pattern and (base near ratio)	US-PGPUB; USPAT	ADJ	ON	2007/07/24 09:37
S2	1146	pattern and (base near ratio) and diameter	US-PGPUB; USPAT	ADJ	ON	2007/07/23 14:22
S3	749	pattern and (base near ratio) and diameter and thickness	US-PGPUB; USPAT	ADJ	ON	2007/07/23 14:22
S4	313	pattern and (base near ratio) and diameter and thickness and exposure	US-PGPUB; USPAT	ADJ	ON	2007/07/23 14:25
S5	39	pattern and (amine near ratio) and diameter and thickness and exposure	US-PGPUB; USPAT	ADJ	ON .	2007/07/23 15:14
S6	39	pattern and (amine near ratio) and diameter and thickness and exposure	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/23 15:49
<b>S7</b>	13701	pattern near forming and acid	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/23 15:50
<b>S8</b>	12296	pattern near forming and acid and method	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/23 15:50
S9	12296	(pattern near forming) and acid and method	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/23 15:50
S10	11101	(pattern near forming)near method	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ò	2007/07/23 15:50
S11	1256	(pattern near forming) near method and thickness and diameter	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/23 15:51
S12	320	(pattern near forming) near method and thickness and diameter and amine	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ .	ON	2007/07/23 15:51
S13	32	(acid near ratio) and (reduction near thickness)	US-PGPUB; USPAT	ADJ	ON	2007/07/24 07:39
S14	1	deffect and (reduction near thickness)	US-PGPUB; USPAT	ADJ	ON	2007/07/24 07:43

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C1F	2470	defeat and (vadueties see	LIC DCDLID	ADI	ON	2007/07/24 07:42
S15	3470	defect and (reduction near thickness)	US-PGPUB; USPAT	ADJ	ON	2007/07/24 07:43
S16	3574	defect and (reduction near thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 07:55
S17	1507	defect and (reduction near thickness) and acid	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 07:55
S18	1033	defect and (reduction near thickness) and acid and base	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON .	2007/07/24 07:55
S19	94	defect and (reduction near thickness) and (acid near base)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 08:01
S20	14	defect and (reduction near thickness) and (acid near ratio)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 08:03
S21	0	defect and (reduction near thickness) and (equaivalent near ratio)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 08:03
S22	24	defect and (reduction near thickness) and (equivalent near ratio)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 08:05
S23	13	surfactant near acid near ratio	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 08:06
S24·	18	surfactant near base near ratio	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON .	2007/07/24 08:15
S25	13	surfactant near acid near ratio	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	ON	2007/07/24 08:15
S26	13	surfactant near acid near ratio	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	OFF	2007/07/24 08:16

S27	349	amine near acid near ratio	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	OFF	2007/07/24 08:17
S28	155	defect and surfactant and (reduction near thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	OFF	2007/07/24 08:29
S29	0	defectnear pattern and (reduction near thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ .	OFF	2007/07/24 08:29
S30	26	defect near pattern and (reduction near thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	OFF	2007/07/24 08:29
S31	16	defect near pattern and (reduction near thickness) and acid	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	OFF	2007/07/24 08:30
S32	0	defect near pattern and (reduction near thickness) and acid near ratio	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	OFF	2007/07/24 08:31
S33	. 0	defect near pattern and (reduction near thickness) and (acid near ratio)	US-PGPUB; USPAT; EPO; JPO; DERWENT	ADJ	OFF	2007/07/24 08:31
S34	3345	pattern near forming near method	US-PGPUB; USPAT	OR	OFF	2007/07/24 09:37
S35	123	phtoresist	US-PGPUB; USPAT	OR .	OFF	2007/07/24 09:38
S36	121989	photoresist	US-PGPUB; USPAT	OR	OFF	2007/07/24 09:38
S37 <sub>.</sub>	1486	S34 and S36	US-PGPUB; USPAT	OR	OFF	2007/07/24 09:38
S38	0	"acid to base"	US-PGPUB; USPAT	OR	OFF	2007/07/24 09:39
S39	320	acid near base near ratio	US-PGPUB; USPAT	OR .	OFF	2007/07/24 09:39
S40	2	S37 and S39	US-PGPUB; USPAT	ADJ	ON	2007/07/24 09:50
S41	. 0	organic acid near ratio near 1:3	US-PGPUB; USPAT	ADJ	ON	2007/07/24 09:51
S42	0	organic acid near ratio near 1:3	US-PGPUB; USPAT	ADJ .	OFF	2007/07/24 09:51

S43	16	acid near ratio near 1:3	US-PGPUB; USPAT	ADJ	OFF	2007/07/24 09:52
S44	1	base near ratio near 1:3	US-PGPUB; USPAT	ADJ	OFF	2007/07/24 10:06
S45	34	(reduction near thickness) and (increase near base)	US-PGPUB; USPAT	ADJ	OFF	2007/07/24 10:08
S46	8	(reduction near thickness) and (increase near base) and resin	US-PGPUB; USPAT	ADJ	OFF	2007/07/24 10:08
S47	761	poly(N-vinylpyrrolidone\$10)	US-PGPUB; USPAT	ADJ	OFF	2007/07/24 10:09
S48	3	poly(N-vinylpyrrolidone\$10) and (develop\$5 near defect)	US-PGPUB; USPAT	ADJ	OFF ·	2007/07/24 10:10

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